



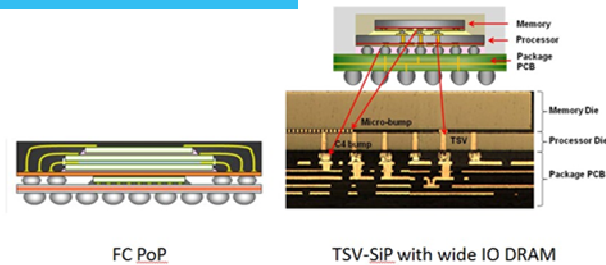
3D-IC is Now Real: Wide-IO is Driving 3D-IC TSV

Samta Bansal and Marc Greenberg, Cadence
EDPS
Monterey, CA
April 5-6, 2012

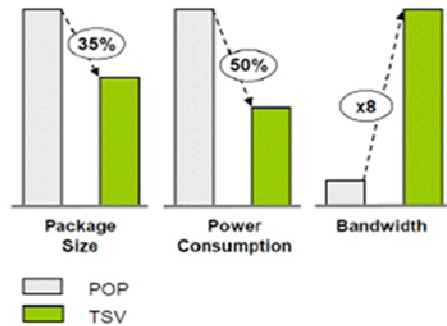
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What the fuss is all about ...

* Source : ECN Magazine March 2011

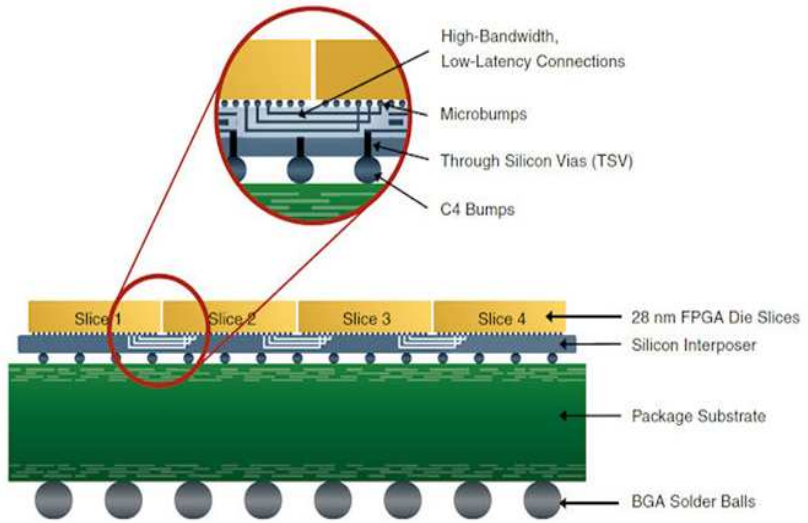


	Conventional 3D Package (FC-PoP) with LPDDR2	TSV-SiP with Wide IO memory
Memory I/O Power Consumption	176 mW	44 mW



Comparison of package performance: wire-bonding PoP vs wide IO interface with TSV (Courtesy of Samsung)

Samsung Wide-IO Memory for Mobile Products - A Deeper Look



* Source : EDN Magazine Sep 2010

**Enables 100x Improvement in Die-to-Die Bandwidth Per Watt
2-3x Capacity Advantage Over Monolithic Devices**

Xilinx brings 3D interconnect to commercialization phase in digital FPGA world

Faster, Denser, Low-power Chips Using 3D-IC TSVs



What and Why: Wide-IO and TSVs?

Customer drivers in the industry

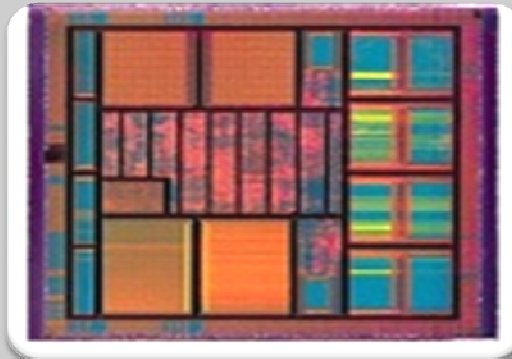
Performance, power and area (PPA) enables end-product differentiation



Mobility is Key: Faster, Denser, Low-power Chips

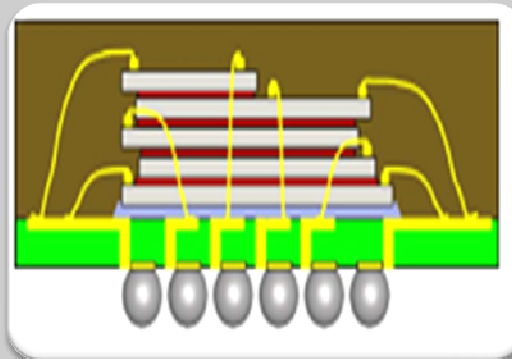
Paradigm shift from 2D SOC to 3D-ICs

Achieving the PPA goals within shorter time-to-market



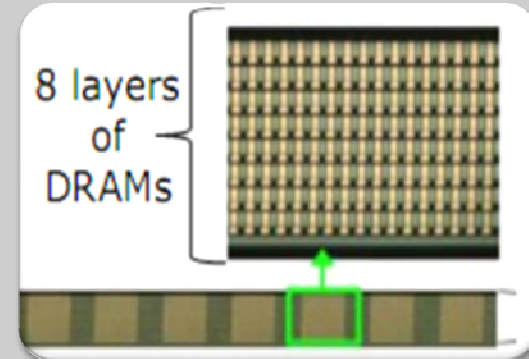
SOC: One Large Die

- **PROS**
 - Most common today
 - Strong ecosystem
 - Cost effective for very high volume production
- **CONS**
 - Long development times
 - "Bet-the-farm" tape-outs
 - NREs and yields < 22 nm?
 - One process for Logic, Memory and Analog?
 - HW difficult to customize



SiP: Multi-Die Wirebonded

- **PROS**
 - Production-proven
 - Mix different processes
 - Build a system quickly
 - HW easily customized
 - Short development time
- **CONS**
 - Bonding needs I/O rings
 - Wires add RLC parasitics - limited power savings
 - Limited speed gains
 - Limited number of layers

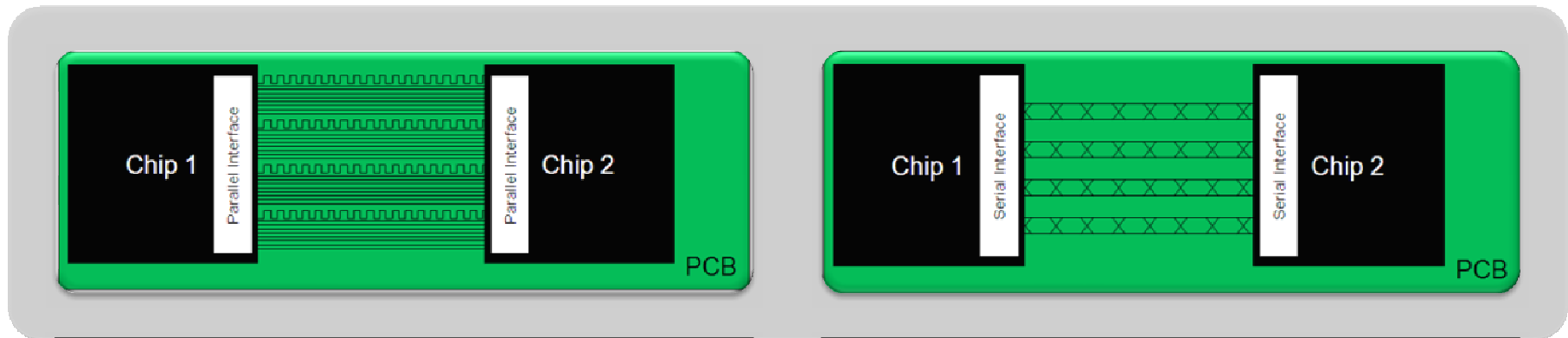


3D-IC TSV: Multiple Die Through Silicon Vias

- **PROS**
 - Densest implementation
 - Low power, high speed
 - Ideal for high complexity
 - Easy to mix processes
 - 1000s of TSVs possible
 - Die- / wafer level-stacking:
 - Flexibility versus unit cost
- **CONS**
 - Ecosystem emerging
 - Volume production ramping
 - Thermal Issues?

CPU to DRAM

Existing inter-die connection methods



Parallel Connection across a PCB

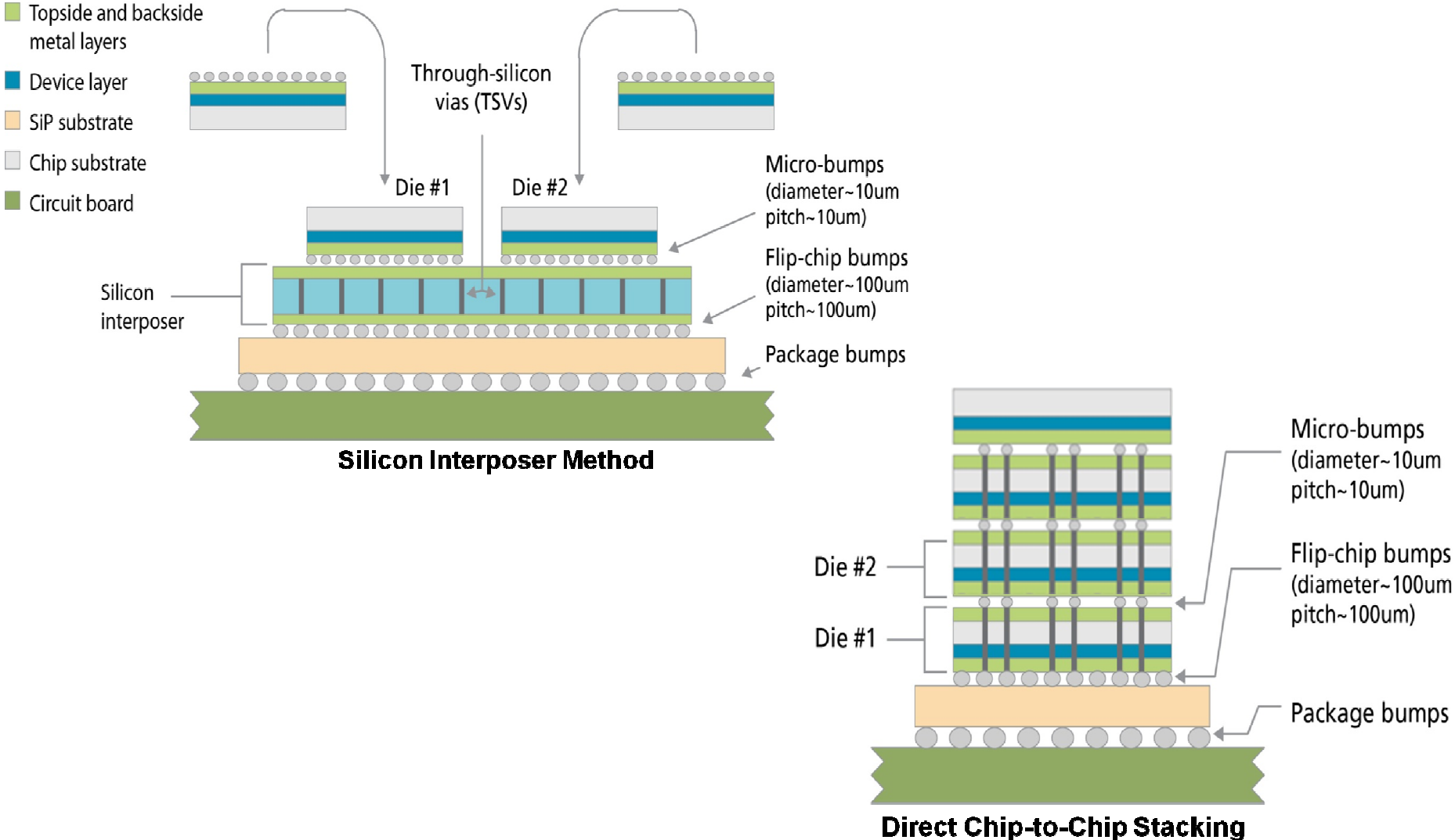
- Most common CPU/SoC-to-DRAM connection today
- Well understood and extensible
- Many pins required for high bandwidth
 - ~60 signal pins for a 32-bit LPDDR2 interface (2012 low-mid range smartphone)
 - ~120 signal pins for a 2-channel LPDDR2 interface (2012 mid-high end smartphone)
 - ~300 signal pins for a 3-channel 64-bit DDR3 interface (2012 PC)

Serial Connection Across a PCB

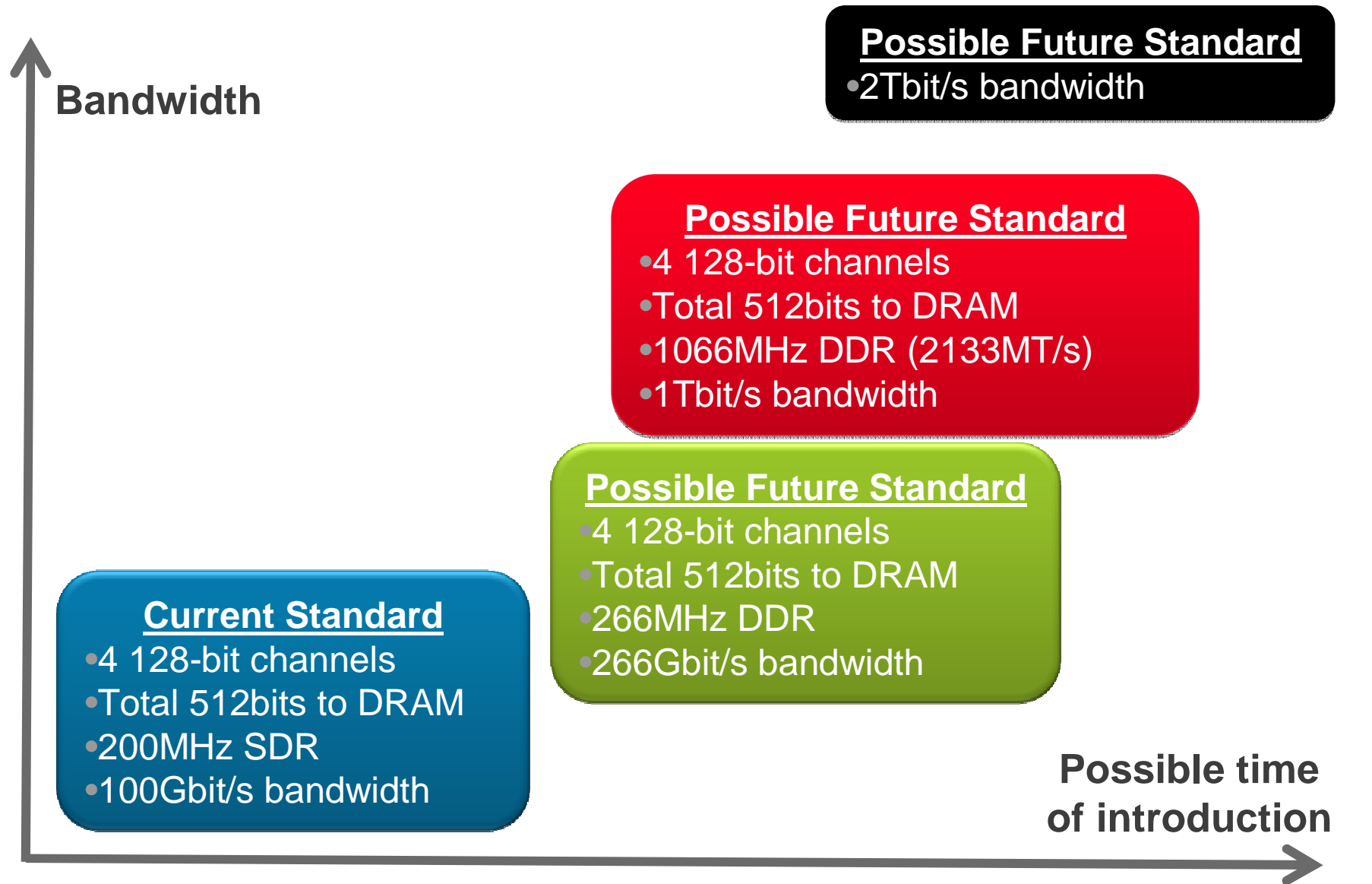
- Fewer pins than parallel connection
- Common for PCIe and other SerDes-based standards
- Can provide data transfer over longer physical distances if needed
- Potential latency and power considerations
- Not commonly used for DRAM at present; future solution?

Pin Count, Power, Latency Concerns?

New inter-die connection method: TSV

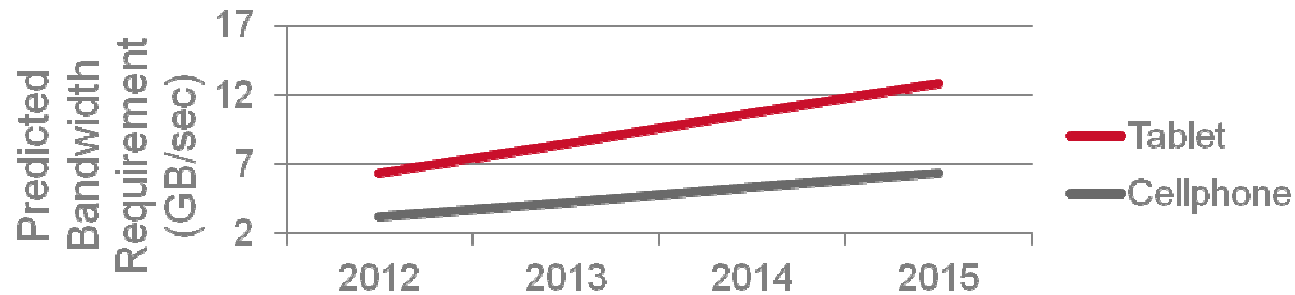


What is Wide-IO DRAM?



Why do you need Wide-IO DRAM?

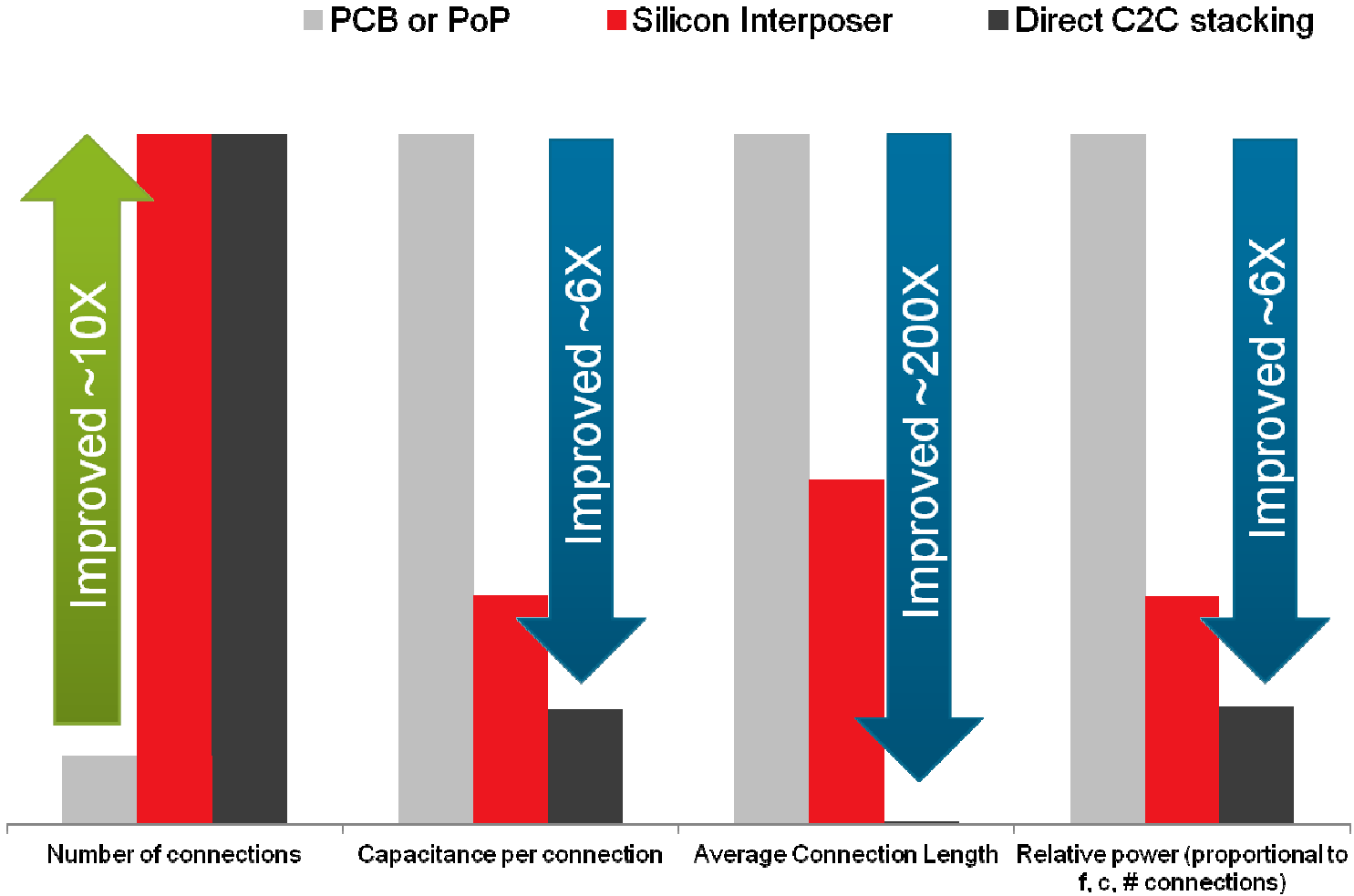
Bandwidth Requirements of Future Mobile Devices



Solutions	LPDDR2 533 MHz		LPDDR3 800 MHz		WideIO 200 MHz	
	Single Channel	Dual Channel	Single Channel	Dual Channel	Single die + LPDDR2	Cube
Density (2014)	2x 4 Gb	4 x 4 Gb	2 x 8 Gb	4 x 8 Gb	2 x 8 Gb	4 x 8 Gb
Bandwidth	4.25 GBy/s	8.5 GBy/s	6.4 GBy/s	12.8 GBy/s	17.1 GBy/s	12.8 GBy/s
Power (burst read)	330 mW	660 mW	430 mW	860 mW	730 mW	540 mW
Power / Bandwidth	78 mW/GByps		67 mW/GByps		43 mW/GByps	42 mW/GByps
Cost (2014)	N/R	1	N/R	1.1	1.2	1.4

- ➔ WideIO provides 2x power efficiency compared to LPDDR2/3
- The initial JEDEC proposal is providing 12.8GBytes bandwidth. Increasing DRAM frequency to 266MHz and implementing dual data rate transfers will provide eventually more than 34GBytes/s.

General benefits of TSVs



Why Wide-IO is driving TSV

DRAM is the ideal candidate to drive TSV technology

- Usually manufactured on a non-logic process
- Requires high bandwidth connection between CPU and DRAM
- Uneconomic or impossible to place large capacity (Gbits) of DRAM on same die as CPU
- Low power connection between dies desirable
- Possibility of different memory configurations using the same CPU die



Implementing Wide IO and TSVs

Real chip, real example walkthrough

Wioming test chip program

Same SoC addressing several schemes of 3D integration



High speed CMOS techno
70mm²
2000 TSVs
1000 bumps
500 balls

	Proof of concept for:		
	Technology	Architecture	Design Flow
<p>Wide IO demonstrator: DRAM on Wioming</p>	<ul style="list-style-type: none"> <input type="checkbox"/> Die to Die <input type="checkbox"/> Face to Back <input type="checkbox"/> TSV middle <input type="checkbox"/> Cu Pillar bumps and micro-bumps 	<ul style="list-style-type: none"> <input type="checkbox"/> Wide memory data bus (512-bit) <input type="checkbox"/> High bandwidth (>10GBps) memory interface <input type="checkbox"/> Multi-channel memory controller <input type="checkbox"/> Test for 3D Memory interconnect 	<ul style="list-style-type: none"> <input type="checkbox"/> 3D floorplanning <input type="checkbox"/> 3D routing (signal & power) <input type="checkbox"/> 3D Test <input type="checkbox"/> Verification <input type="checkbox"/> Power analysis <input type="checkbox"/> Thermal analysis
<p>3D NoC demonstrator: Wioming on Wioming</p>	<ul style="list-style-type: none"> <input type="checkbox"/> Die to Die <input type="checkbox"/> Face to Back <input type="checkbox"/> TSV middle <input type="checkbox"/> Cu Pillar bumps and micro-bumps 	<ul style="list-style-type: none"> <input type="checkbox"/> 3D NoC router <input type="checkbox"/> 3D serial link <input type="checkbox"/> Test for 3D NoC interconnect <input type="checkbox"/> TSV Fault Tolerance scheme 	
<p>3 Layer demonstrator: DRAM on Wioming on Wioming</p>	Combination of all above techniques		

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A Three-Layers 3D-IC Stack including WideIO and 3D NoC

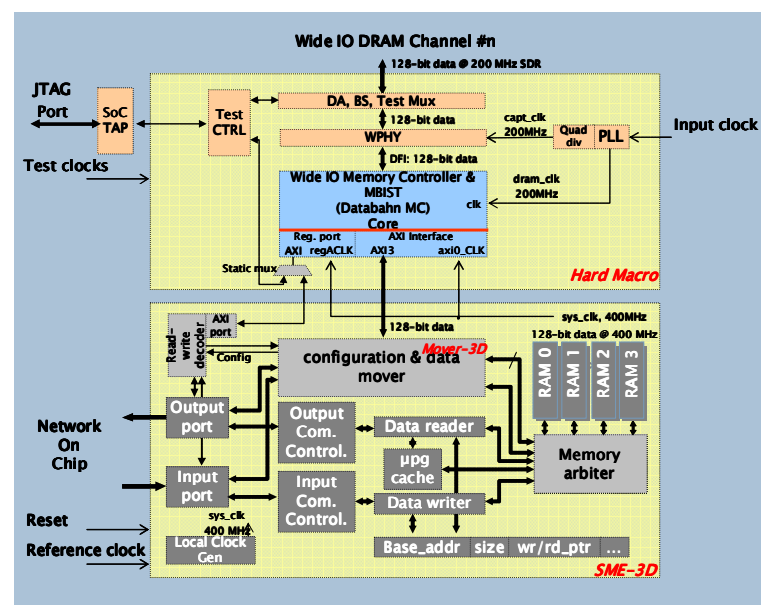
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Wide IO SME architecture overview

- Wide IO Memory Controller (Cadence DENALI)
 - Compliant with DRAM specification for Wide IO from JEDEC (<http://www.jedec.org/>)
 - High performance, and advanced low-power features
 - First deliveries to 3D-IC Wioming ST-Ericsson/LETI project
- Wide IO PHY Interface
 - 200MHz, 128 bit, SDR
 - ~1200 TSVs, μ buffers and μ bumps
 - Also integrates ESD protections for DRAM
- Specific Design for Wide IO Testability Integration
 - Boundary scan, direct access, stuck-at, memory bist, PLL test
- Smart Memory Engine
 - Data transfer handling between Wide IO, SRAM and ANoC
 - Integration within ANoC
 - Up to 3.2GB/s data bandwidth



Cadence Wide-IO DRAM controller

Challenges	Solutions
Merge existing and new technology	<ul style="list-style-type: none">• Start with extensible, high performance, low-power base architecture (Supports DDR1, DDR2, DDR3, LPDDR1, LPDDR2 and now DDR4)<ul style="list-style-type: none">• Re-add SDR support• Add new Wide IO feature support• Create DFI extensions for Controller-PHY connection
New testing requirements	<ul style="list-style-type: none">• Extend BIST engine to test for new classes of error
Verification	<ul style="list-style-type: none">• Create memory model of Wide-IO device in Cadence VIP tools• Extend existing configurable verification environment for Wide IO

Overview of tool and methodology

3D Technology & Design Kit

- Target technology
 - Uses ST-Microelectronic
 - Uses TSV middle (Ø)
 - Is a Flip-Chip packa
 - Is a Face2Back, Die
- Back End kit
 - Virtuoso tech file ad
 - EDI Techno file & ca
 - DRC & LVS « 3D » ad

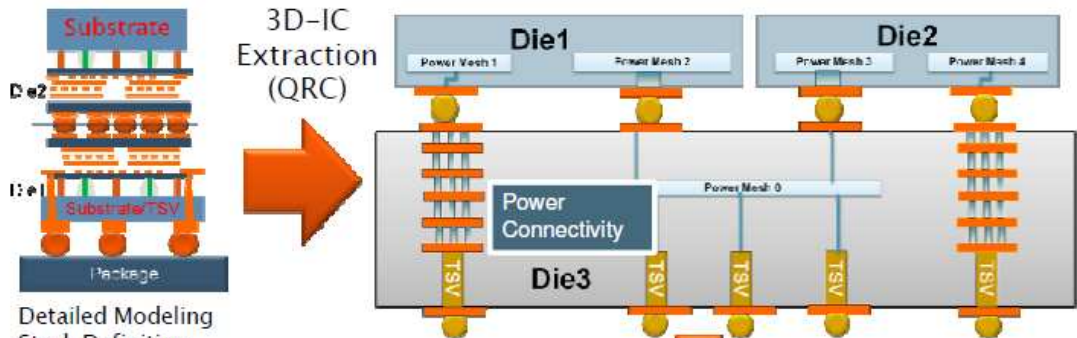
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A Three-Layers 3D-IC Stack including Wide

EDI 3D-IC Stack Design Implementation & Analysis

- Cadence Encou... implementation is collaboration with advanced system
- Supports a comp... for both implem...
 - Different types of bump, copper p... backside metal l...
 - Multiple set of m...
- Supports multiple design implem...
 - Silicon interpose
 - Vertical stack.
 - Mixed stack.
- EDI Design meth... are proven with s...

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A Three-Layers 3D-IC Sta...

EDI 3D-IC Analysis Methodology

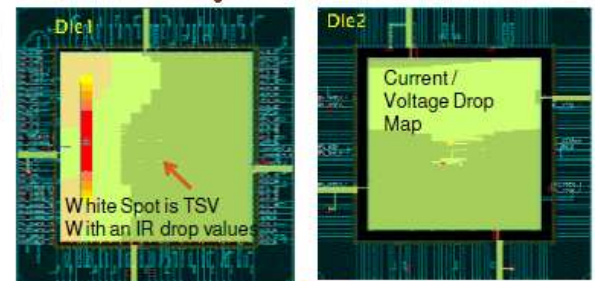


Detailed Modeling Stack Definition

Encounter Timing System (ETS)

Component	TSV	Die	Power Mesh
..._TSV_1	1.000	0.000	0.000
..._Die1	0.000	1.000	0.000
..._PowerMesh0	0.000	0.000	1.000
..._Die2	0.000	0.000	0.000
..._PowerMesh1	0.000	0.000	1.000
..._PowerMesh2	0.000	0.000	1.000
..._PowerMesh3	0.000	0.000	1.000
..._PowerMesh4	0.000	0.000	1.000
..._Die3	0.000	0.000	0.000

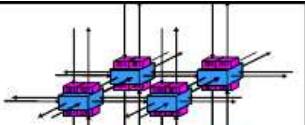
Encounter Power System (EPS)



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Overview of tool and methodology

3D-ANoC TSV Floorplanning



• 3D-ANoC TSV d

- Symmetrical 3D NoC conn
- 3D NoC matrix also con

• EDI 10.1 tool fl

- Use automated TSV crea

- set die to botto
- Create the TSV
- Assign TSV + b
- save TSV & bac
- set die to top
- create front Bu

- Then, use semi-autom

- PG connections b
- μ - Buffer cell plac
- PG routing withi
- ESDs, etc ...

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3D-IC : Power & IR drop analysis

• Using Encount

- Currently using
- No sign-off mod

• Power analysis

- Top chip power
- according to tar

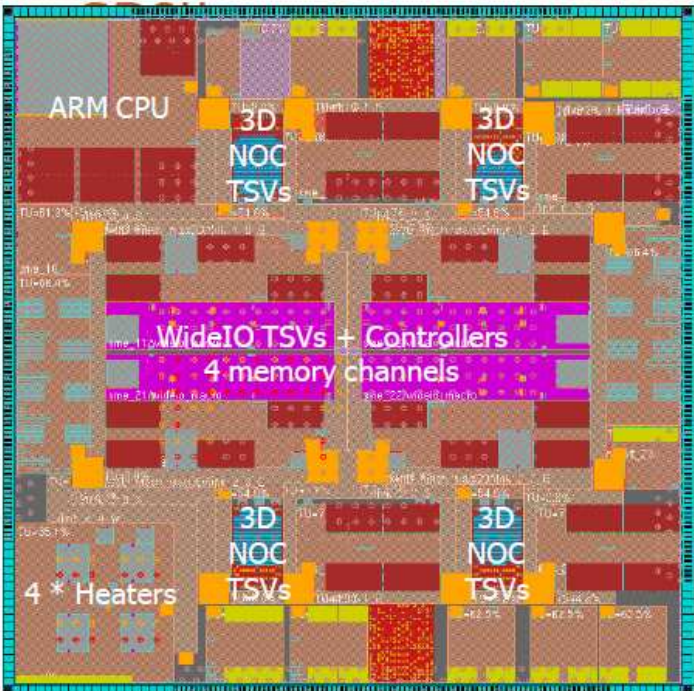
• 3D IR-Drop and

- Bottom Die
- => supplied from th
- supplies
- 0.02 mV m

- Top Die
- => supplied from th
- supplies
- 0.2 mV ma

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Wioming Final



Circuit Technology

- High speed CMOS TSV middle process
- Face2Back, Die2Wafer, Flip-Chip 3DAssembly

Main features

- WideIO memory controllers
- 3D ANOC
- 3GPP LTE multi core CPU backbone
- ARM host CPU

Circuit numbers

- 125 Million Transistors
- 400 Macros
- 270 pads
- 1980 TSV for 3D NoC
- 1250 TSV for WideIO memory
- 985 Bumps for flip chip

Circuit performances

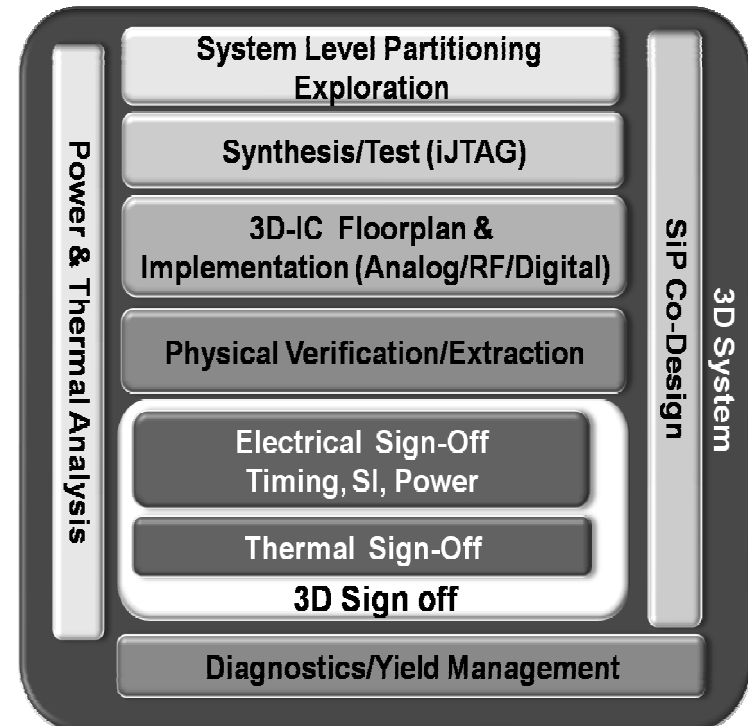
- WideIO 200MHz / 512 bits
- Units in the [350 - 400] MHz range
- Asynchronous NoC ~ 550 MHz

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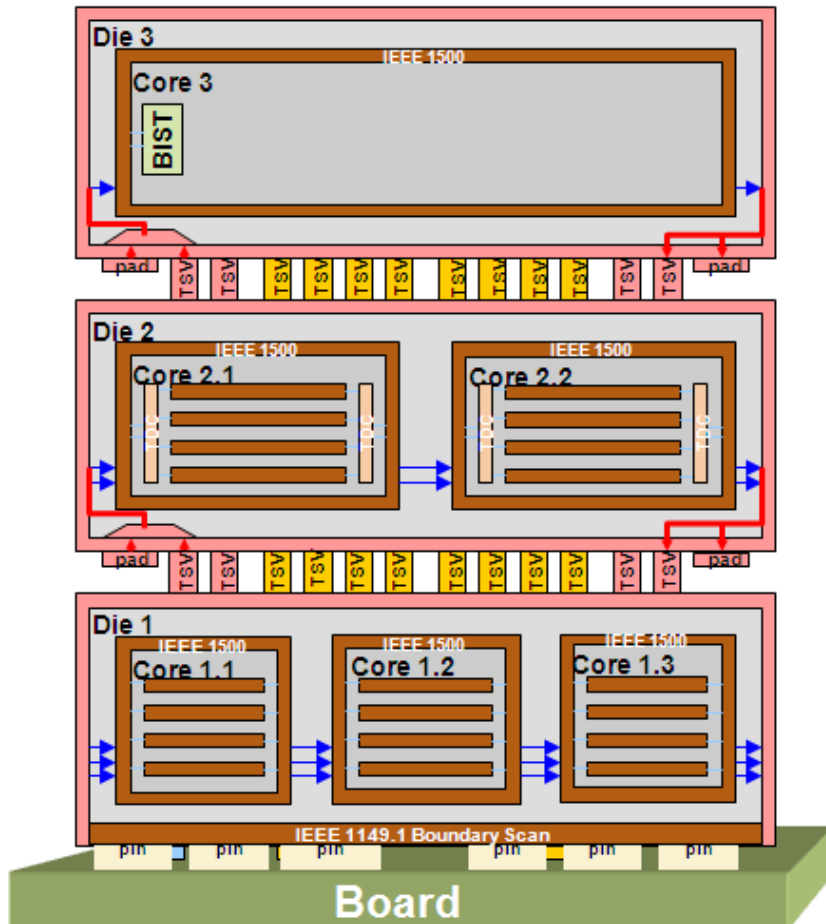
Cadence silicon-proven 3D-IC solution

Plan → implement → test → verify

- Allows heterogeneous integration to offer power, performance in smallest form factor
- **Cadence is technology leader providing complete and integrated 3D-IC solution**
 - Plan->implement->test->verify
 - 1st to market wide I/O memory controller
- **Developed in close partner-collaboration** for past 5 years with leading foundries and customers
- **Multiple 3D-IC tapeouts**
 - Multiple testchip experience: Memory over logic (28 nm), logic over analog, logic over Logic, 3-stack dies
 - Production design tapeout in mid-2010



SiP DFT /3D package test



3D DFT on Die-Level

- Insertion of 3D wrapper
- Creating Test patterns
- Verification and Simulation

Testing Die Interconnects

- ATPG for die interconnects

Testing Die in a Stack

- Modular Test approach
- ATPG-on-top test approach



Challenges in Implementation: Wide IO and TSVs

What are the challenges?

- Manufacturing Wide-IO DRAM and assembly:
 - Test memory wafer after production using FC bumps
 - Thin the wafer to ~50-100um thickness
 - Form TSVs and fill with metal
 - Requires elevated temperatures – extra anneal step
 - Apply backside metal and bumps
 - No opportunity to test here
 - Backside metal bump pitch too fine for most tester heads
 - Handle dies while avoiding mechanical damage
 - They are now the approximate aspect ratio of a postage stamp
 - Attach dies (and interposers, if present) together
 - Does it still work?

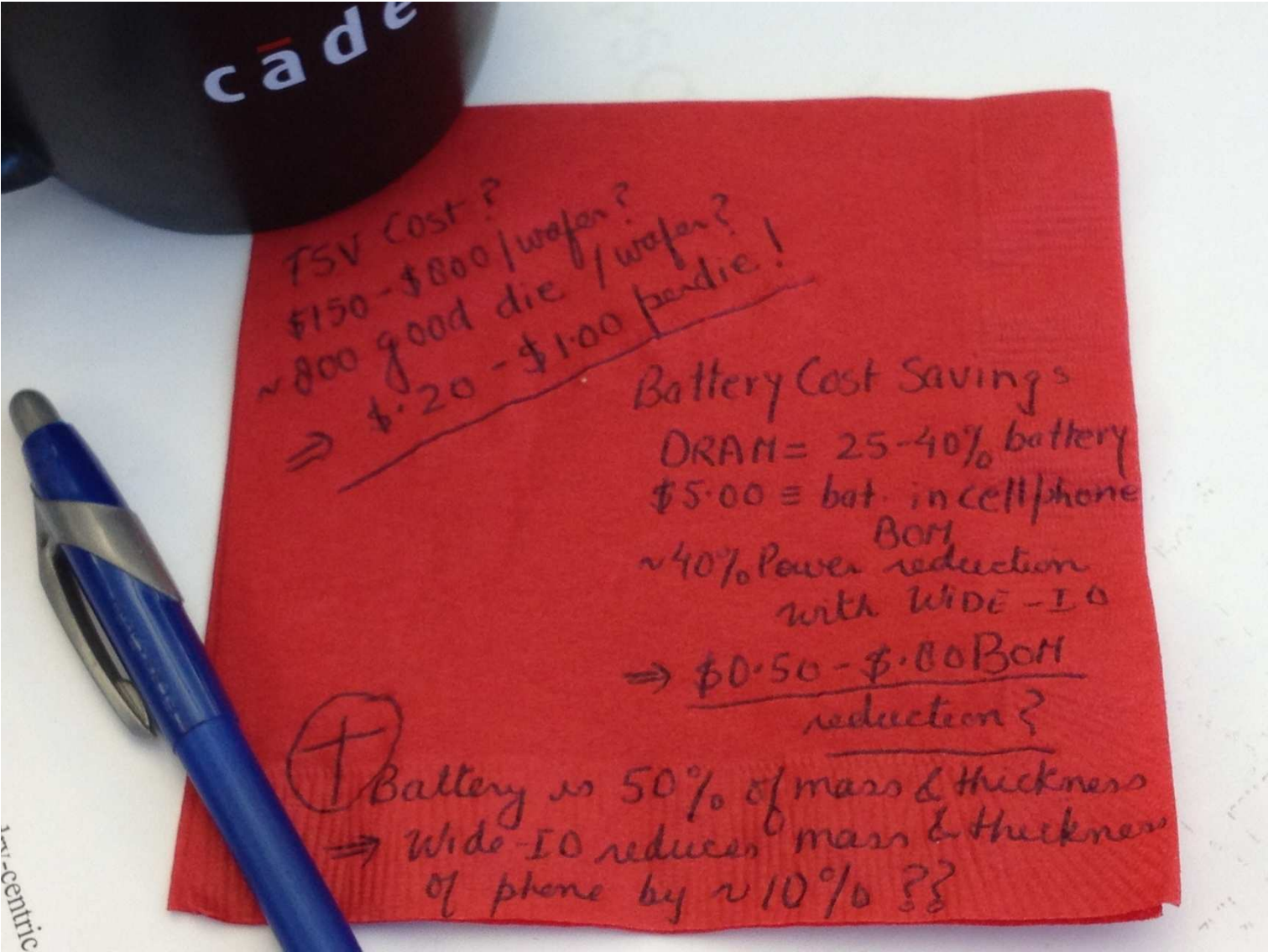
What are the challenges?

- Thermal Issues:
 - Where does the heat go?
- Ecosystem Issues:
 - How many parties involved in stack production?
 - How are responsibilities divided?
 - How are liabilities divided?



Cost !!!

Back of the napkin calculation



Conclusion

- Wide-IO and TSV are real
- Cadence believes that Wide-IO DRAM is the technology that will drive adoption of TSV
- Cadence stands ready with EDA tools and IP to enable your TSV designs with real experiences and partnerships with ~8 testchips and 1 production chip already completed.



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